Femtosecond laser ablation (FESLA) XPS – A novel XPS depth profiling technique for optical/electrical thin films and multi-layered structures

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A comparison of the Ti 2p peak for FESLA XPS, Ar^+ and Ar_n^+ bombardment during depth profiling of TiO_2 showing the retention of chemical state information for FESLA XPS whilst Ar^+ and Ar_n^+ result in the preferential sputtering of oxygen.